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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/707,704	01/06/2004	HANN-JYE HSU	11964-US-PA	1703
31561 75	03/10/2005		EXAM	INER
JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE 7 FLOOR-1, NO. 100 ROOSEVELT ROAD, SECTION 2 TAIPEI, 100			ERDEM, FAZLI	
			ART UNIT	PAPER NUMBER
			2826	
TAIWAN	TAIWAN		DATE MAILED: 03/10/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/707,704	HSU ET AL.			
Office Action Summary	Examiner	Art Unit			
1	Fazli Érdem	2826			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 3 after SIX (6) MONTHS from the mailing date of this communication - If the period for reply specified above is less than thirty (30) date of the period for reply specified above, the maximum statute - Failure to reply within the set or extended period for reply will, Any reply received by the Office later than three months after earned patent term adjustment. See 37 CFR 1.704(b).	ATION. 7 CFR 1.136(a). In no event, however, may a recation. ays, a reply within the statutory minimum of third bry period will apply and will expire SIX (6) MON, by statute, cause the application to become AB	eply be timely filed by (30) days will be considered timely. THS from the mailing date of this communication. SANDONED (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed of	on 21 December 2004.				
	☐ This action is non-final.	•			
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4) ☐ Claim(s) 1-18 is/are pending in the app 4a) Of the above claim(s) is/are v 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 9-12 and 15-18 is/are rejected 7) ☐ Claim(s) 13 and 14 is/are objected to. 8) ☐ Claim(s) are subject to restriction	withdrawn from consideration.				
Application Papers					
9) The specification is objected to by the Examiner.					
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for a) All b) Some * c) None of: 1. Certified copies of the priority document of the certified copies of the priority document of the certified copies of the certified copies of the application from the International * See the attached detailed Office action for the certified copies of the certified co	cuments have been received. cuments have been received in A the priority documents have been Bureau (PCT Rule 17.2(a)).	pplication No received in this National Stage			
Attachment(s)					
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)					
 Notice of Draftsperson's Patent Drawing Review (PTO-3) Information Disclosure Statement(s) (PTO-1449 or PTO Paper No(s)/Mail Date 		s)/Mail Date Informal Patent Application (PTO-152)			

DETAILED ACTION

Allowable Subject Matter

1. Claims 13 and 14 objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 9-12 and 15-18 rejected under 35 U.S.C. 103(a) as being unpatentable over Chang et al. (6,754,105) in view of Hwang (6,699,757) further in view of Forbes et al. (2004/0004245).

Regarding Claims 9-12 and 15-18, Chang et al. disclose a trench sidewall charge trapping dielectric flash memory device where in Fig. 2, it is disclosed trench structures 46 disposes inside p-well 54. Gates 66a and 66b are completely covered with dielectric layer 48. This dielectric layer 48 is between the charge trapping layers 50b' and 50a'. Furthermore, dielectric layer 58 is outside charge trapping layers. Source/drain regions are labeled 62a and 62b. Change et al. fail to disclose the required plurality of source/drain diffusion regions and the required source/drain regions on both sides of the trench. However, Hwang discloses a method for manufacturing embedded non-volatile memory with sacrificial layers where in Figs. 9 and 10, the required plurality of source/drain diffusion regions are shown. Furthermore, Forbes et al. disclose a memory

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utilizing oxide-conductor nanolamination where in Fig. 3, source/drain regions 302-1 and 302-2 are located on both sides of trench 340.

Regarding Claim 12, Figs 9 and 10, disclose the required spacer structures.

It would have been obvious to one of having ordinary skill in the art at the time the invention was made to include the required plurality of source/drain diffusion regions and the source/drain regions on both sides of trench in Chang et al. as taught by Hwang and Forbes respectively in order to have a semiconductor memory structure with better performance.

Conclusion

4. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (571) 272-1914. The examiner can normally be reached on M - F 8:00 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

FE March 5, 2005

> NATHAN J. FLYNN SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 2800